Electronic Supplementary Information

Experimental section

Materials: Nickel foam (NF) was provided by Hangxu Filters Flag Store, Hengshui, Hebei. 4,4'-Biphenyl dicarboxylic acid ($C_{14}H_{10}O_4$) was purchased from Shanghai Haohong Scientific Co., Ltd. N,N-dimethylformamide (DMF) and NiCl₂·6H₂O were purchased from Aladdin Ltd. in Shanghai. Hydrochloric acid (HCl) and C_2H_5OH were purchased from Chengdu Kelon Chemical Reagent Factory. RuO₂ was purchased from Shanghai Macklin Biochemical Co., Ltd. Nafion (5 wt%) solution was purchased from Sigma-Aldrich Chemical Reagent Co., Ltd. All chemical regents were used as received without further purification. The water used throughout all experiments was purified through a Millipore system.

Preparation of the Ni-MOF/NF: The in situ growth of Ni-MOF nanosheet array on NF was carried out via a one-step solvothermal reaction. A piece of NF was first treated with 1 M HCl, ethanol and deionized water by ultrasonic cleaning sequentially before use. 0.4 mmol NiCl₂·6H₂O (0.0951 g) and 0.4 mmol C₁₄H₁₀O₄ (0.0969 g) were dissolved in 25 mL DMF to form a solution, 2.5 mL ethanol and 2.5 mL deionized water were added slowly to the solution under constant stirring. Then the solution was transferred to a 40 mL Teflon-lined stainless-steel autoclave in which a piece of treated NF (2.5 × 4 cm) was immersed into the solution. The autoclave was sealed and maintained at 125 °C for 8 h in an electric oven to obtain Ni-MOF/NF. After the autoclave cooled down naturally, the Ni-MOF/NF was taken out and washed with water and ethanol for several times, followed by drying 12 h at 60 °C.

Preparation of the RuO₂/NF: 20 mg commercial RuO₂ and 40 μ L 5 wt% Nafion solution were dispersed in 960 μ L ethanol/water (v/v = 3:1) followed by 30 min sonication to form a homogeneous ink. Then 20 μ L ink was loaded onto a NF (0.5 × 0.5 cm) and dried under ambient condition (RuO₂ loading: 1.6 mg cm⁻²). The Ni-MOF powder/NF electrode was also prepared according to above method.

Characterizations: XRD pattern was obtained from a Shimazu XRD-6100 diffractometer with Cu K α radiation (40 kV, 30 mA) of wavelength 0.154 nm (Japan).

XPS measurements were performed on an ESCALABMK II X-ray photoelectron spectrometer using Mg as the exciting source. SEM measurements were carried out on a XL30 ESEM FEG scanning electron microscope at an accelerating voltage of 20 kV.

Electrochemical measurements: Electrochemical measurements were performed with a CHI 660E potentiostat (CH Instruments, China) in a standard three-electrode setup with the prepared samples as the working electrode, a graphite rod as the counter electrode, the Hg/HgO electrode as the reference electrode. The OER activity was evaluated using linear sweep voltammetry (LSV) with a sweep rate of 5 mV s⁻¹. Electrochemical impedance spectroscopy (EIS) was measured at a frequency between 0.1 Hz and 10⁶ Hz. The tests were performed in 1 M KOH Solution. All the potentials were displayed versus reversible hydrogen electrode (RHE) by the formula: E (RHE) = E (Hg/HgO) + 0.098 + 0.059 × pH.



Fig. S1. Atomic structural diagram of Ni-MOF.



Fig. S2. SEM image of Ni-MOF nanosheet.



Fig. S3. XRD pattern for Ni-MOF scratched down from NF.



Fig. S4. SEM image of Ni-MOF powder.



Fig. S5. A local view of the LSV curves for Ni-MOF/NF and Ni-MOF powder/NF.



Fig. S6. SEM image of Ni-MOF/NF after the oxidation of Ni^{2+} to Ni^{3+} before OER.



Fig. S7. Time-dependent current density curve for Ni-MOF/NF.



Fig. S8. SEM image of Ni-MOF/NF after OER electrolysis.



Fig. S9. CVs of (a) Ni-MOF/NF and (b) Ni-MOF powder/NF under different scan rates increasing from 20 to 80 mV s⁻¹ in 1.0 M KOH. Linear relationship of the oxidation peak currents vs. scan rates for (c) Ni-MOF/NF and (d) Ni-MOF powder/NF.



Fig. S10. (a) Ni-MOF/NF and (b) Ni-MOF powder/NF in the non-faradaic capacitance current range at scan rates increasing from 20 to 80 mV s⁻¹. (c) and (d) the capacitive currents at 0.15 V vs. Hg/HgO as a function of scan rate for Ni-MOF/NF and Ni-MOF powder/NF.

| Catalyst | j (mA cm ⁻²) | η (mV) | Electrolyte | Ref. |
|--|--------------------------|---------|-------------|-----------|
| Ni-MOF/NF | 20/100 | 350/450 | 1.0 M KOH | This work |
| Ni ₃ N/NF | 100 | 470 | 1.0 M KOH | 1 |
| Ni/CTF | 10 | 374 | 1.0 M KOH | 2 |
| ALD NiS _x | 10 | 372 | 1.0 M KOH | 3 |
| β-Ni(OH) ₂ | 10 | 444 | 1.0 M KOH | 4 |
| NiOOH | 10 | 525 | 1.0 M KOH | 5 |
| NiOOH nanosheets | 10 | ~370 | 1.0 M KOH | 6 |
| NiO/NF | 10 | 390 | 1.0 M KOH | 7 |
| Ni-MOF/NF | 10 | 362 | 1.0 M KOH | 8 |
| Co _x Ni _{7-x} | 10 | 370 | 1.0 M KOH | 9 |
| NiCo LDH | 10 | 367 | 1.0 M KOH | 10 |
| CoNi SUNOE | 10 | 450 | 1.0 M KOH | 11 |
| NiCo ₂ O ₄ nanoneedles | 10 | 565 | 1.0 M KOH | 12 |
| Fe-Ni oxide | 10 | >375 | 1.0 M KOH | 13 |
| Fe ₃ Pt/Ni ₃ FeN | 10 | 370 | 1.0 M KOH | 14 |

 Table S1. Comparison of OER performance for Ni-MOF/NF with other Ni-based
 electrocatalysts in alkaline media.

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